

FIG.1A

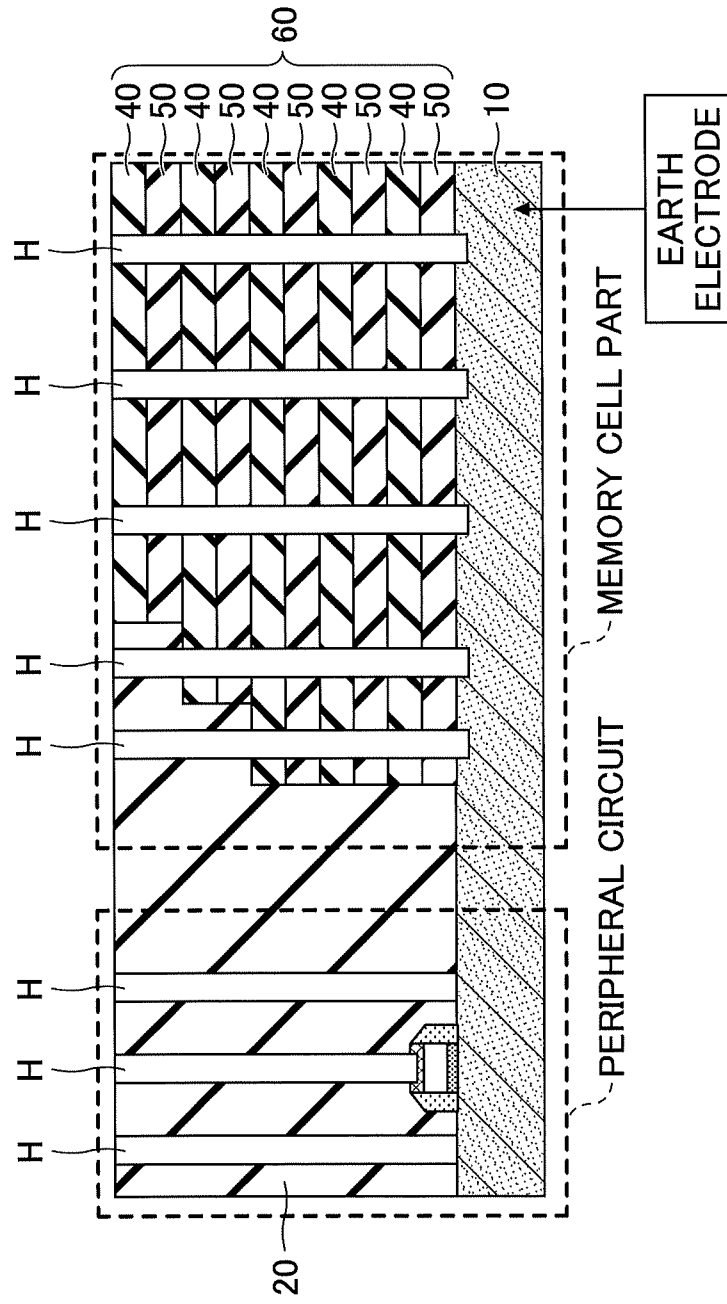
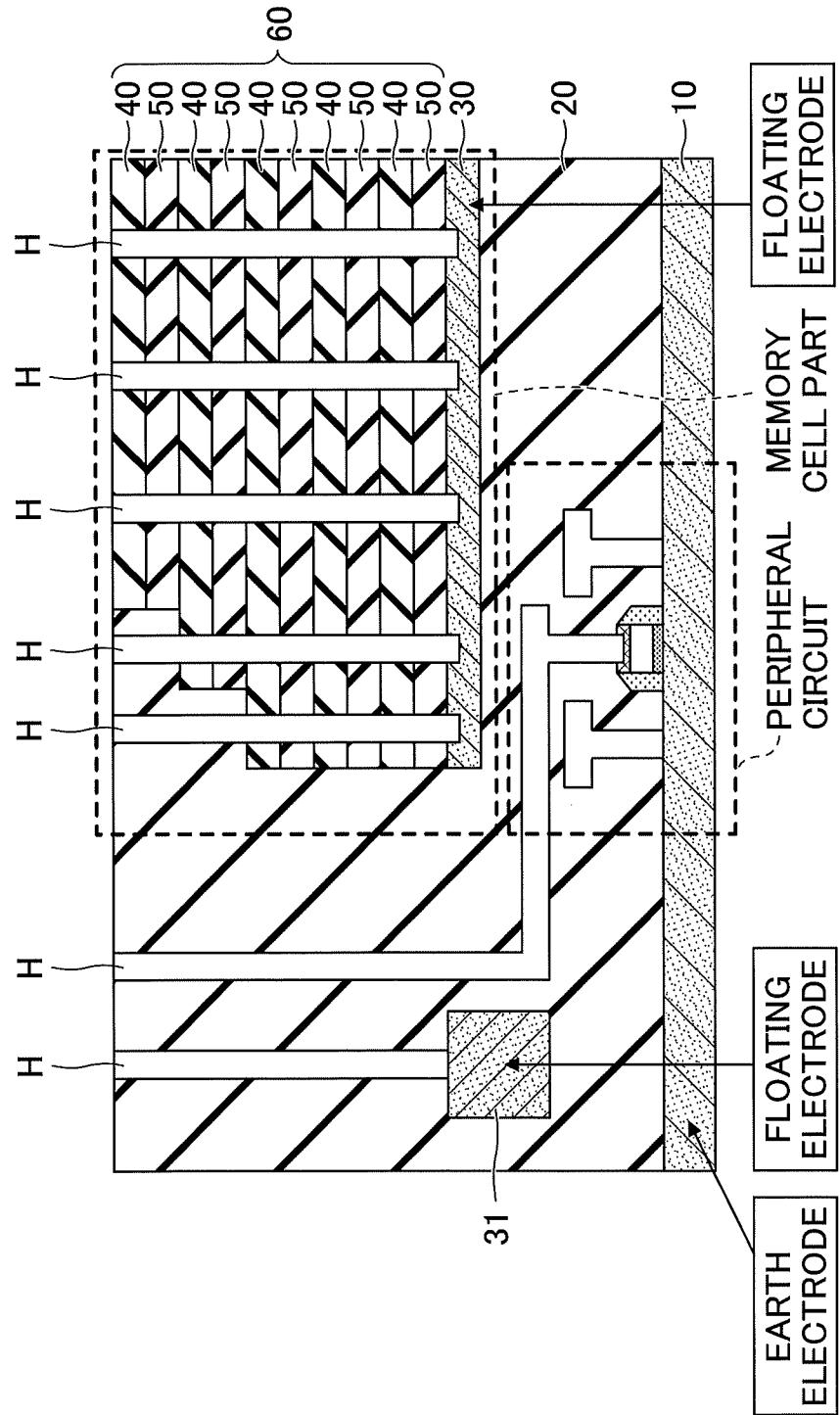
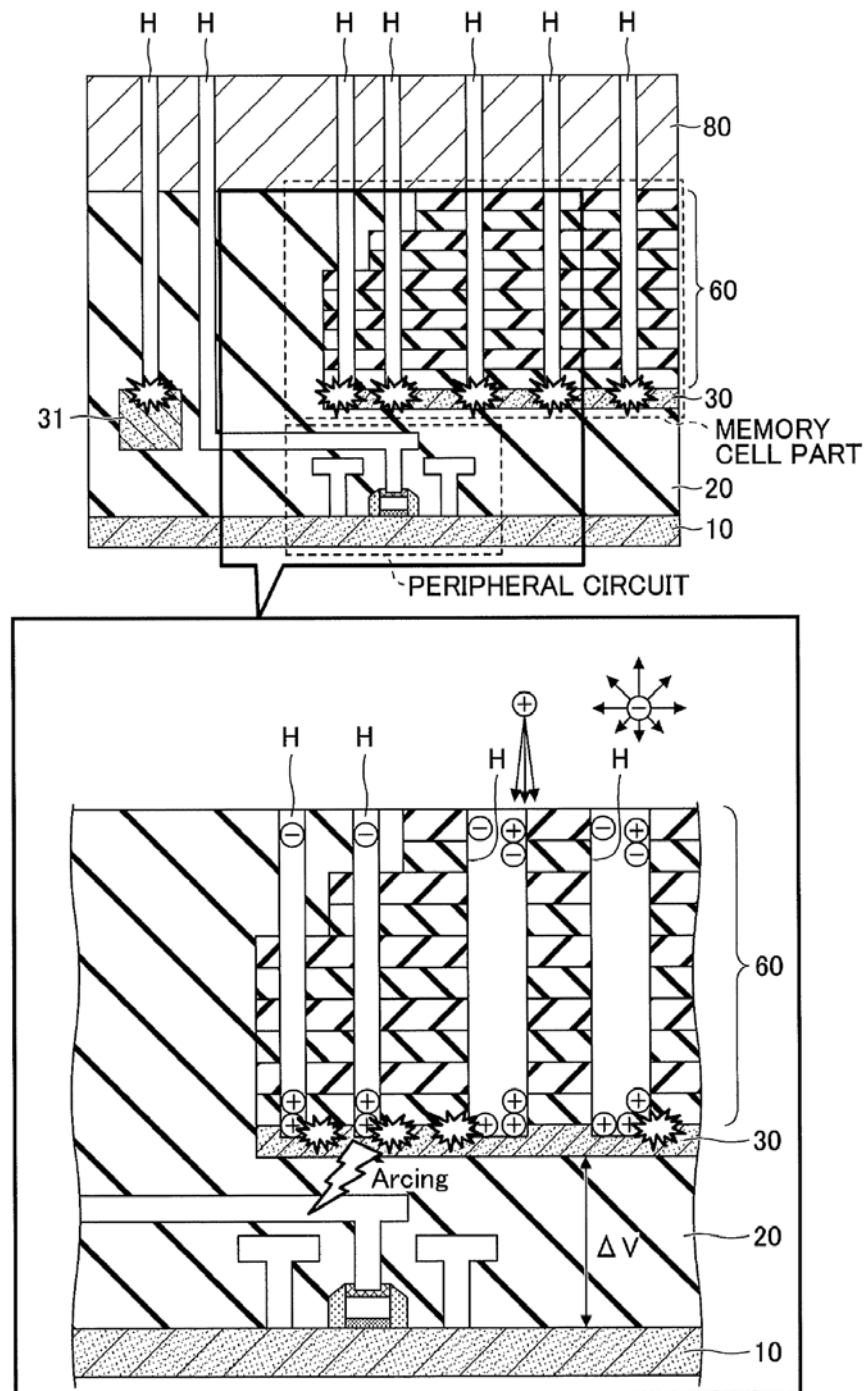


FIG.1B



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FIG.2



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FIG.3

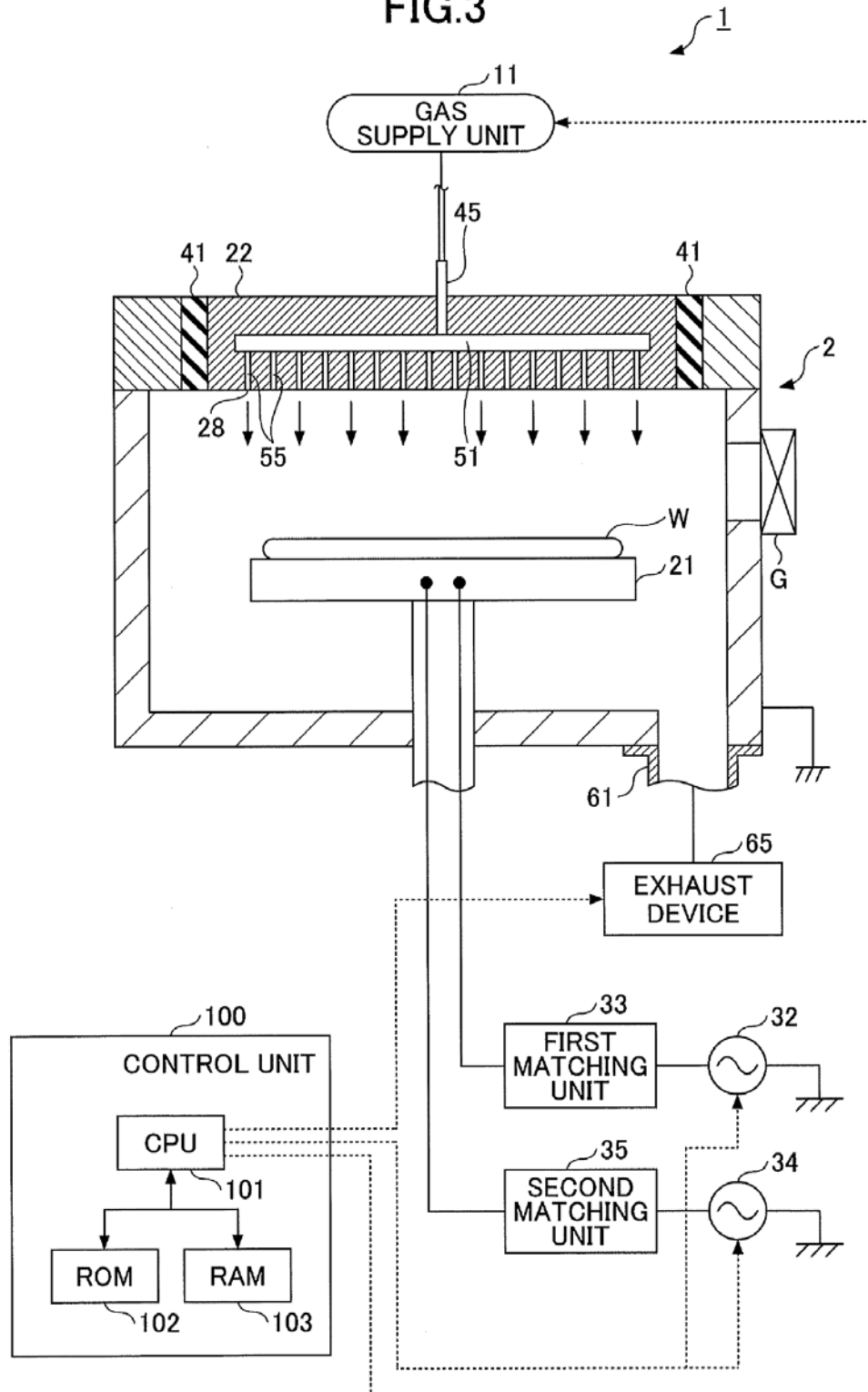


FIG.4

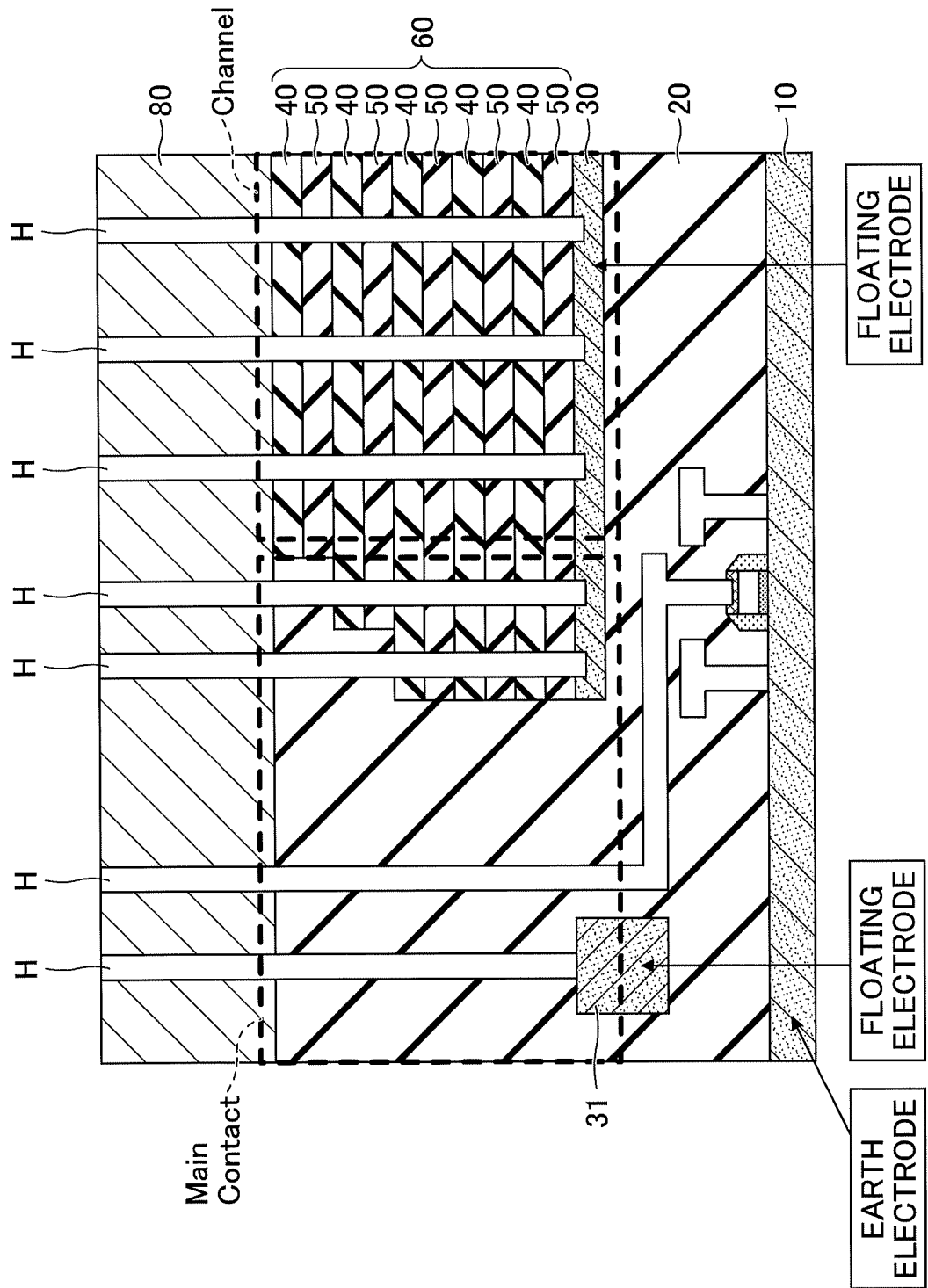


FIG.5B

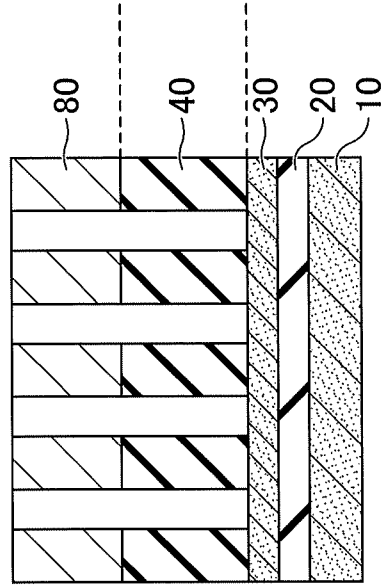


FIG.5A

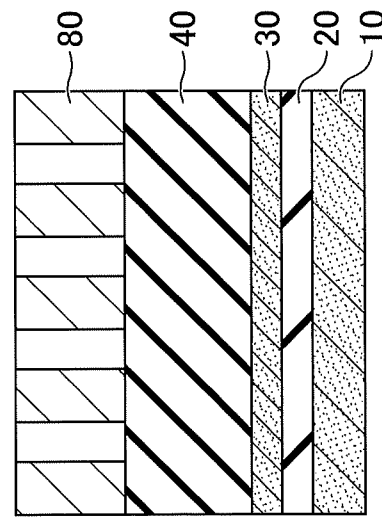
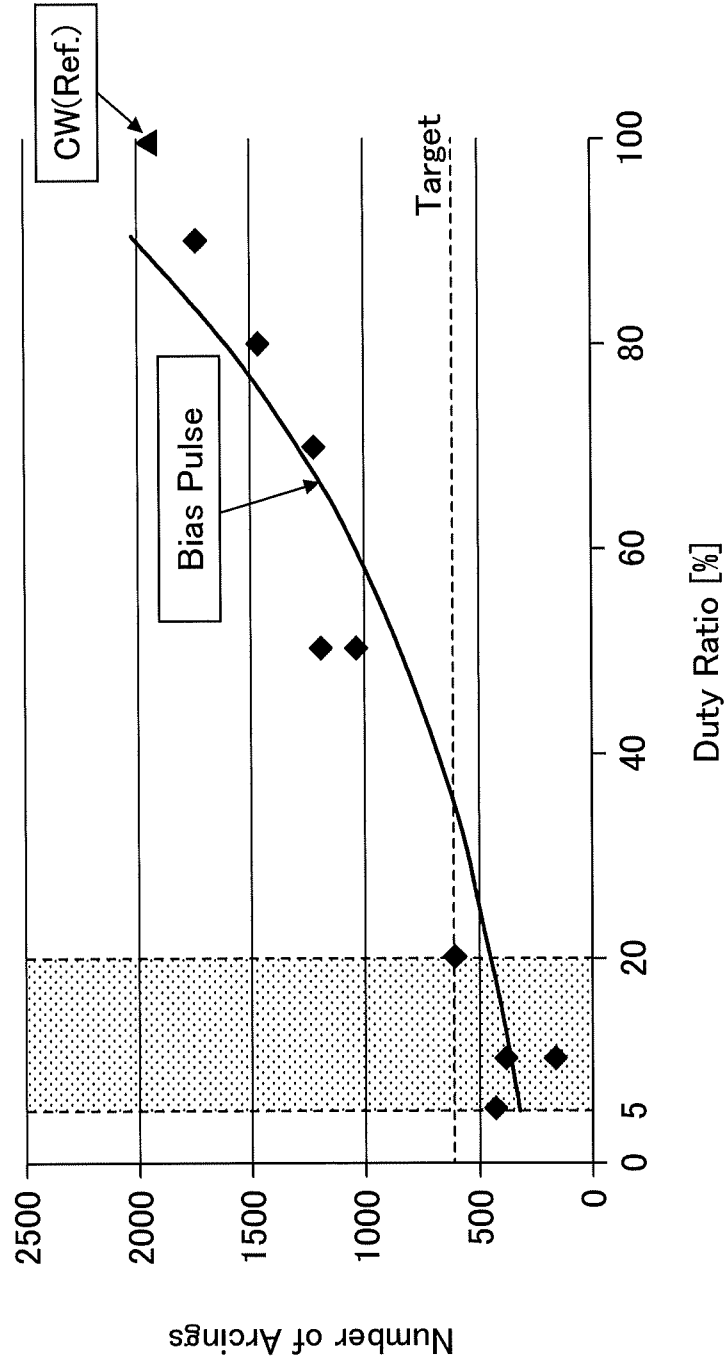


FIG.5C



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FIG.6A

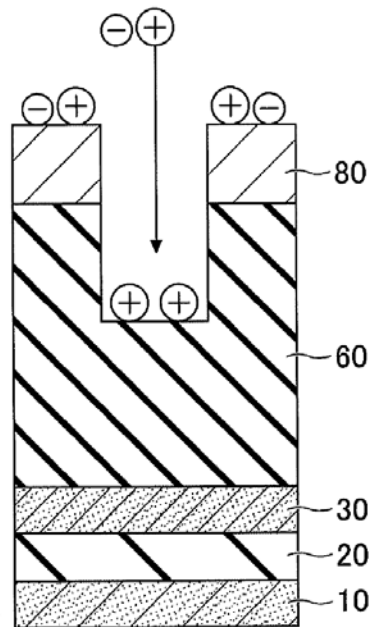
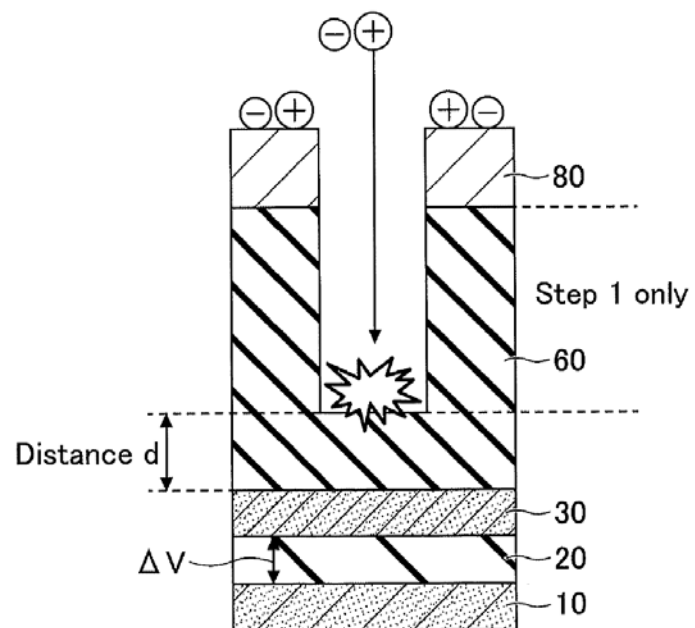
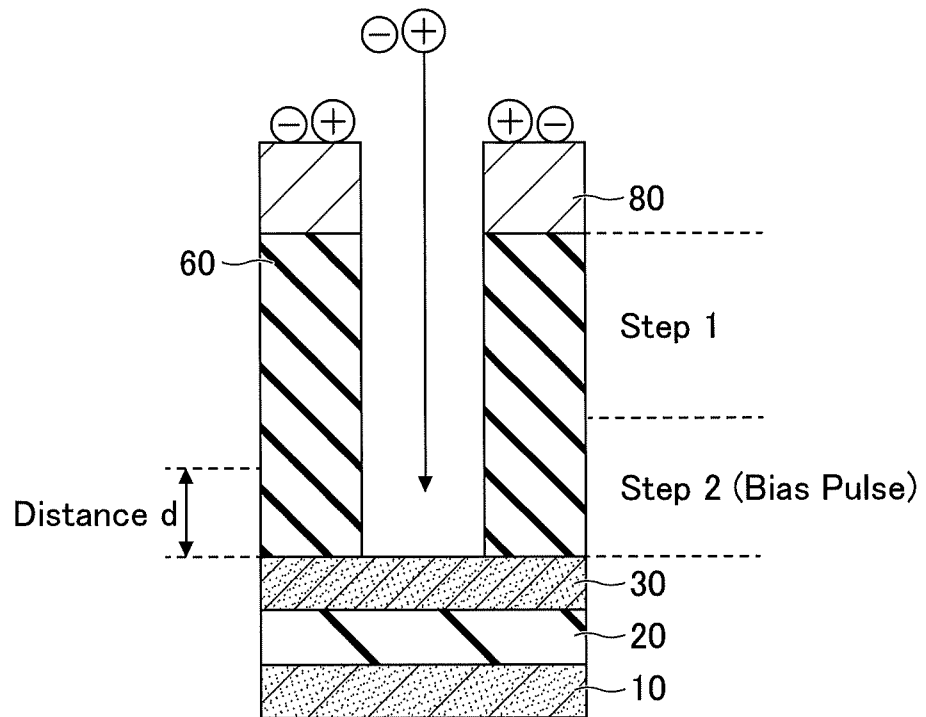


FIG.6B



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FIG.6C



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FIG.7

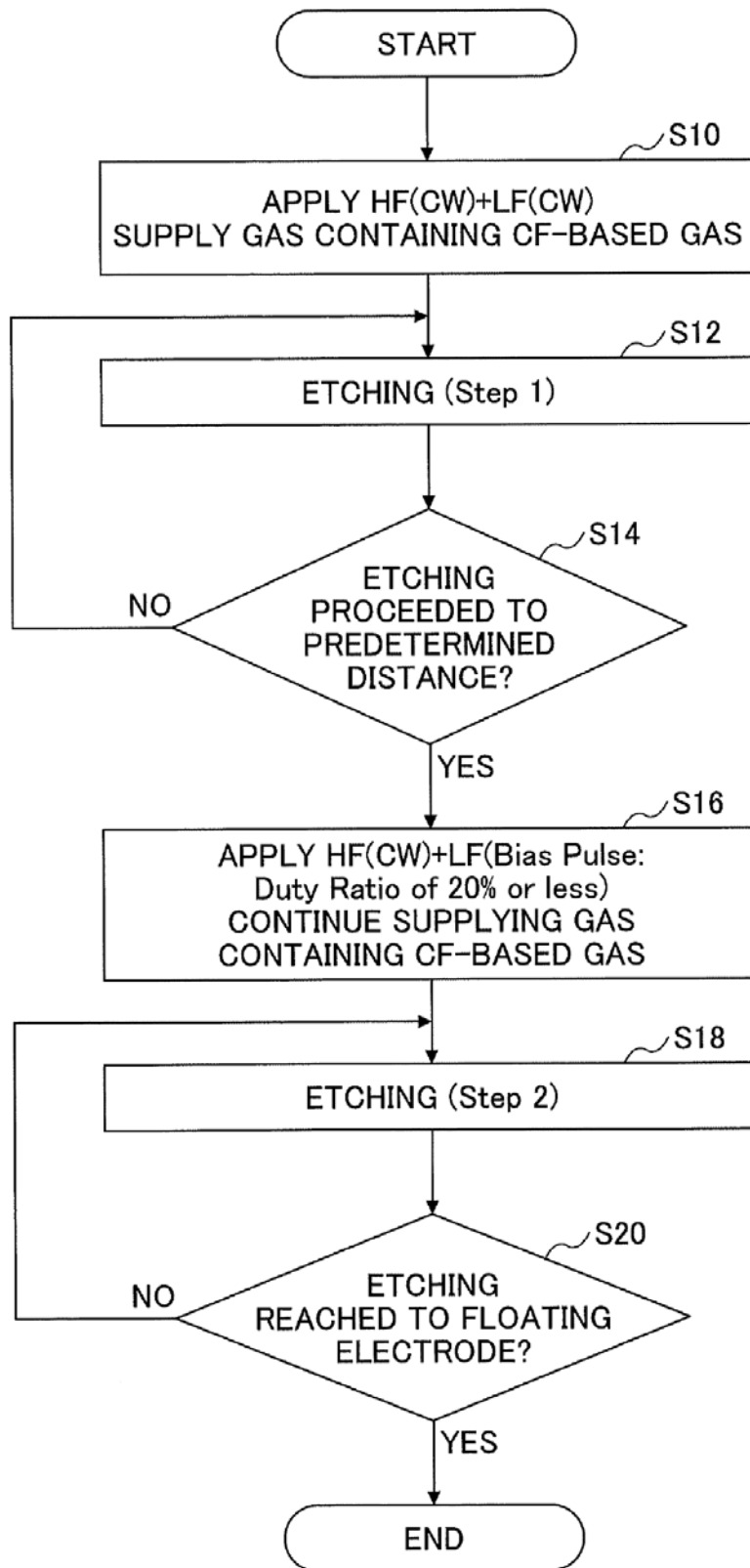


FIG.8

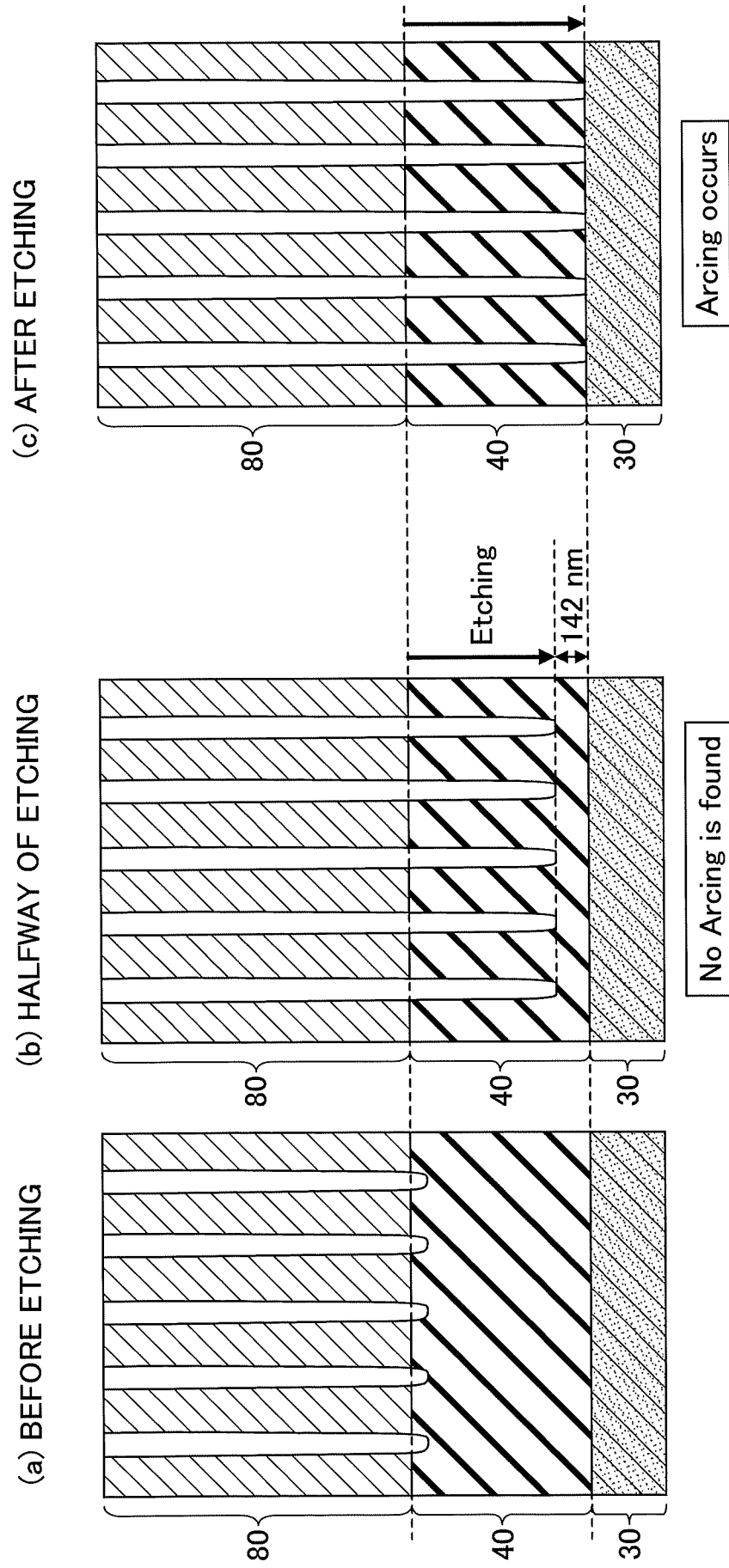
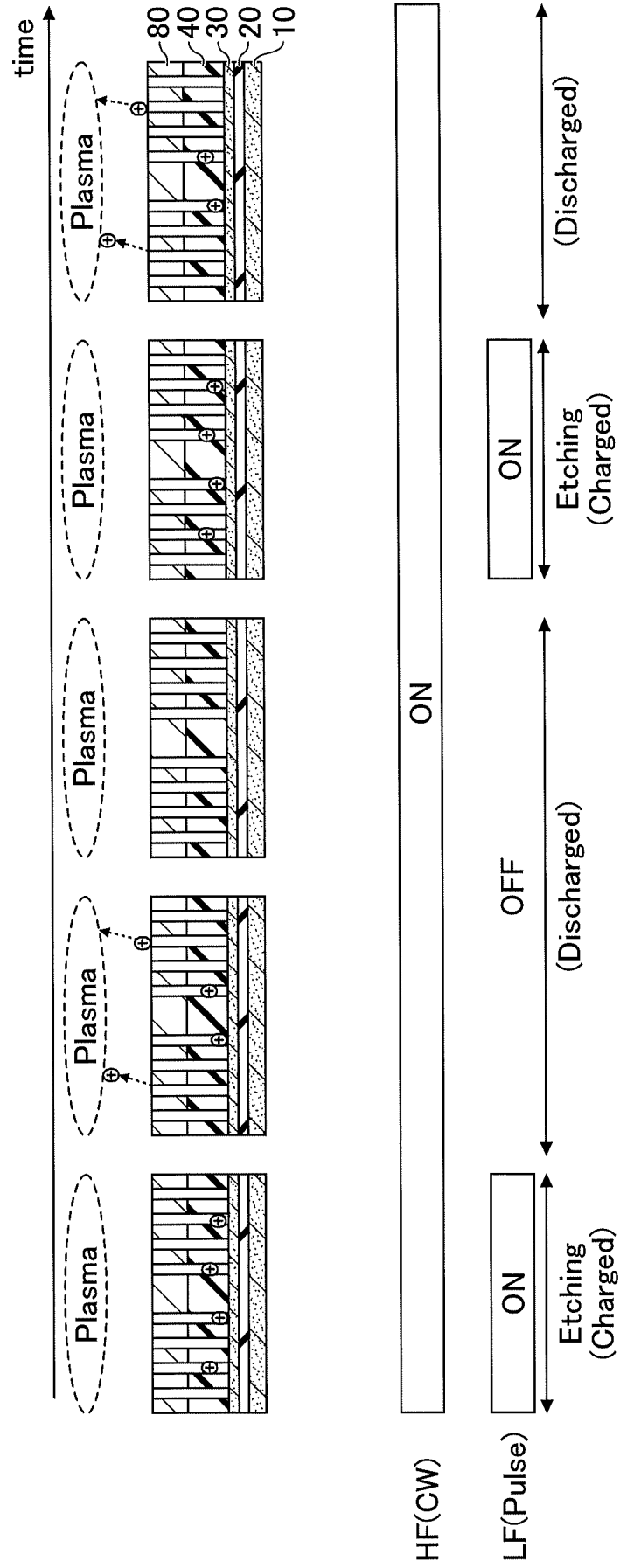


FIG.9



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FIG.10A

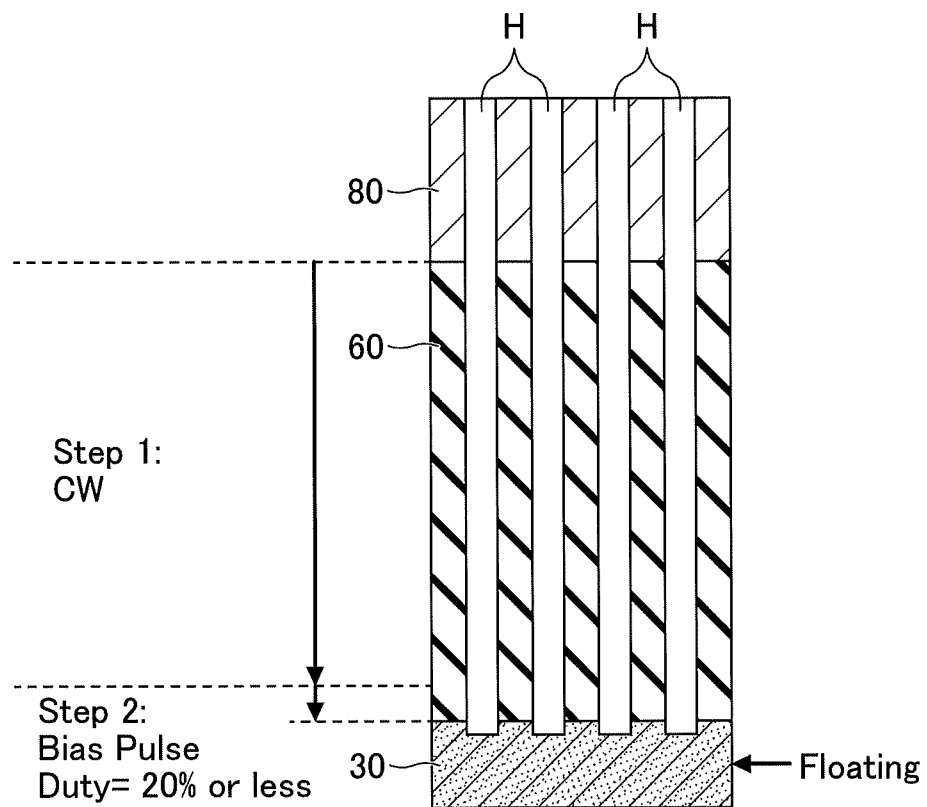


FIG.10B

	Step 1	Step 2
	CW	Bias Pulse Duty Ratio= 10%
Etching Rate SiO ₂ = 700 nm	572 nm/min	103 nm/min
Mask Selectivity SiO ₂ /Carbon	5.5	2.9
Shading Damage Number of Arcings	1779	150